

## Abstract of the Disclosure

An object of the present invention is to stably supply  
a treatment chamber with a treatment gas with a  
5 prescribed composition. A spin on dielectric (SOD)  
system includes a film treatment apparatus of the  
present invention which comprises, for forming an  
interlayer insulating film, a treatment chamber for  
placing a wafer W, a first mass flow controller for  $\text{NH}_3$   
10 gas, a second mass flow controller for  $\text{N}_2$  gas with a  
prescribed water vapor, thereby supplying the treatment  
chamber with a gas of a prescribed composition.